Supplies Provided by NUFAB

**Gowning**

All required gowning supplies

**Personal Protective Equipment (PPE)**

All required PPE

**Chemicals**

- Photoresists: SPR220.7, SU8-2050, SU8 25, SU8 2, SU8-2010, S1813, S1805, LOR 1A, LOR 5A, AZ 5214E-IR, AZ P4620, 495 PMMA A8, Polyimide PI2545
- Developers: MF319, AZ 400K (1:4 and concentrated), SU8 Developer, AZ 917MIF
- Resist Removers: Remover 1165, Nanostrip
- Adhesion Promoter: HMDS, MCC Primer 80/20 (20% HMDS and 80% PM Acetate)
- Solvents: Acetone, 2-Propanol
- Acids: Chrome Etchant, Buffered Oxide Etch 6:1, Aluminum Etchant, Nanostrip, HF, Fe₂O₃ Etchant, Copper Etchant, Gold Etchant TFA

**General Cleanroom Supplies**

- Silicon Wafers (various sizes)
- Wafer and Mask Holders (various sizes)
- Cleanroom Notebooks
- Cleanroom Paper
- Cleanroom Wipes (two types)
- Storage Boxes
- Petri Dishes
- Aluminum Foil

**Equipment Specific Supplies**

- AJA Sputter Targets: Cu, Al, Cr, Ti, Ni, W, Si, SiO₂, Si₃N₄, ZnO, ITO, PZT, Zn/Al₂O₃ (2% by weight)
- AJA E-beam Evaporator: Crucibles for all materials
- Denton Thermal Evaporator: Boats for all materials, chrome-coated tungsten rods
- Evaporation Materials: Mo, W, Ag, Al, Cu, Ni, Ti, Cr, Au
- Mask and Maskless Aligners: Blank Photomasks (for mask making) 4"x4" (Cr), 5"x5" (Cr), 3"x3" (Fe₂O₃), 4"x4" (Fe₂O₃), 5"x5" (Fe₂O₃)

**Gases**

- Silane, Ammonia, Hydrogen, Dichlorosilane, Forming Gas (4%H₂, Balance N₂), UHP nitrogen, Oxygen, N₂O, CF₄, C₄F₈, CHF₃, Helium, SF₆, Argon, Liquid CO₂

Updated: 9/1/2017